



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Timothy J. Brosnihan et al

Art Unit : 2814

Serial No. : 09/342,348

Examiner : Anh D. Mai

Filed : June 29, 1999

Title : METHOD OF FABRICATING A MICROFABRICATED HIGH ASPECT RATIO
DEVICE WITH ELECTRICAL ISOLATION

Commissioner for Patents
Washington, D.C. 20231

RESPONSE

In response to the action mailed June 6, 2001, please amend the application as follows:

In the title:

Please amend the title to read: METHOD OF FABRICATING A
MICROFABRICATED HIGH ASPECT RATIO DEVICE WITH ELECTRICAL ISOLATION.

In the claims:

Please amend the claims as follows:

1. (Amended) A method of fabricating a microelectromechanical system,
comprising:
- providing a substrate having a device layer;
 - etching a first trench in the device layer, the first trench surrounding a first region
of the substrate;
 - depositing a dielectric isolation layer in the first trench to electrically isolate the
first region from a second region of the substrate; and
 - etching a second trench in the device layer, the second trench located in first
region and defining a microstructure.

CERTIFICATE OF MAILING BY FIRST CLASS MAIL

I hereby certify under 37 CFR §1.8(a) that this correspondence is being
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